CLAIMS

1. A method of calibrating modification of optical devices, comprising the steps of providing a mask with a predetermined pattern, projecting radiation through the mask so as to form a patterned projected image; and comparing a pattern of the projected image with a pattern of the mask to determine deviations of the projected image from the image of the mask.

2. A method as defined in claim 1, wherein said comparing includes comparing a size of the projected image with the size of the image on the mask.

3. A method as defined in claim 1, wherein said providing the mask includes providing a mask which has at least two fields each having a plurality of features spaced from one another in one direction so that the directions of spacing of the features in said two fields are transverse to one another.

4. A method as defined in claim 3, wherein said features in each of said field are evenly spaced from one another.

5. A method as defined in claim 3, wherein said features in each of said fields are parallel to one another.

6. A method as defined in claim 3; and further comprising arranging the mask so that said features of at least one of said fields are aligned with a principal axis of the optical device.

7. A method as defined in claim 3, wherein said features are arranged so that a spacing between the features of one of said fields is different from the spacing of said features of the other of said fields.

8. A method as defined in claim 1; and further comprising moving an article on which the image is projected relative to the optical device so as to produce a plurality of images with a plurality of patterns, said comparing includes comparing the plurality of patterns of the plurality of images with the pattern of the mask.

9. A method as defined in claim 1, wherein said obtaining of the projected image includes providing a substrate, projecting the pattern through the mask on the substrate, and obtaining the projected image on the substrate.

10. A method as defined in claim 1, wherein said obtaining of projected image includes passing the radiation through the mask and obtaining an electronic image with a pattern, said comparing includes comparing the pattern of the electronic image with the pattern of the mask.

11. A method as defined in claim 1, wherein said comparing includes comparing a deviation of a magnification of the pattern and the image relative to the pattern of the mask from a standard deviation.

12. A method as defined in claim 1, wherein said providing includes forming a mask by an optical source producing an interference pattern corresponding to the desired pattern of the mask.

13. A method as defined in claim 1, wherein said providing includes producing the mask by an optical source which generates an interference pattern and acts on a chemical substance to cause etching of corresponding areas of the mask so as to produce the desired pattern of the mask.